

**MODULATED LITHOGRAPHIC BEAM TO REDUCE
SENSITIVITY TO FLUCTUATING SCANNING SPEED**

ABSTRACT

A lithographic apparatus capable of reducing sensitivity to fluctuating scanning speed and improve lithographic scanning processing time, is presented herein. In one embodiment, the apparatus comprises a modulator that modulates a patterned lithographic beam based on the scanning speed as the beam and substrate move relative to each other. The modulator is configured to modulate an attribute of a patterned lithographic beam, such as, the intensity or size of the beam.